

**Listing of the Claims:**

Claims 1-17 (Canceled).

18. (Currently Amended) A method of fabricating a liquid crystal display device comprising:

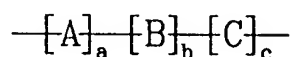
preparing a first substrate and a second substrate;

forming a photo-alignment layer ~~at least~~ on the first substrate, wherein the photo-alignment layer has an ethenyl group ~~[[at]]~~ in a main chain; and

forming a liquid crystal layer between the first and second substrates.

19. (Original) The method of claim 18, wherein the photo-alignment layer is formed of a material having a photo-reactive ethenyl group on a polymer main chain, wherein the polymer is denoted by the following chemical formula 1:

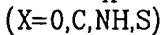
{chemical formula 1}



wherein subscripts a, b, and c denote a component ratio of respective monomers, wherein  $0 < a \leq 1$ ,  $0 \leq b < 1$ , and  $0 \leq c < 1$ , and wherein component A, which is a monomer including the photo-reactive ethenyl group, is selected from groups designated in chemical formula 2, substituted-structure groups of the chemical formula 2 with a halogen, cyano, nitro, amino group, and other substituted-structure groups with an alkyl and haloalkyl, and cyanoalkyl group having 1 to 10

carbons or an aryl, alkyl, aryl, haloaryl, haloalkyl aryl, nitroaryl, cyanoaryl group having 3 to 8 carbons;

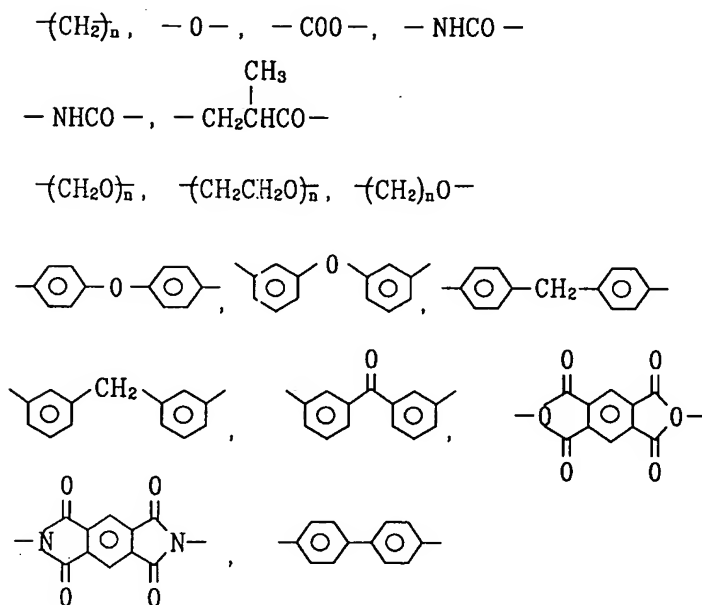
{Chemical Formula 2}



independently from groups shown in chemical formula 3, substituted-structure groups of the chemical formula 3 with a halogen, cyano, nitro, amino group, other substituted-structure groups

with carbonated groups of which carbon number n lies between 1 and 10 such as an alkyl, haloalkyl, and cyanoalkyl, and other carbonated groups of which carbon number lies between 3 and 8 such as an alkylaryl, haloaryl, haloalkylaryl, nitroaryl, cyanoaryl;

{Chemical Formula 3}



21. (Original) The method of claim 18, further comprising:

forming a gate line and a crossing data line on the first substrate;

forming a thin film transistor at a crossing between the gate and data lines; and

forming a pixel electrode connected to the thin film transistor.

22. (Original) The method of claim 18, wherein the photo-alignment layer is formed by light-irradiation.

23. (Original) The method of claim 22, wherein the light-irradiation is irradiated at least once.

24. (Original) The method of claim 22, wherein the light is selected from a group consisting of unpolarized light, non-polarized light, linearly polarized light and partially polarized light.

25. (Currently Amended) A method of fabricating a liquid crystal display device comprising:

preparing a first substrate and a second substrate;

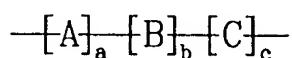
forming a photo-alignment on the first substrate, wherein the photo-alignment layer includes an ethenyl group  $[[at]]$  in a main chain;

forming a rubbing alignment layer on the second substrate; and

forming a liquid crystal layer between the first and second substrates.

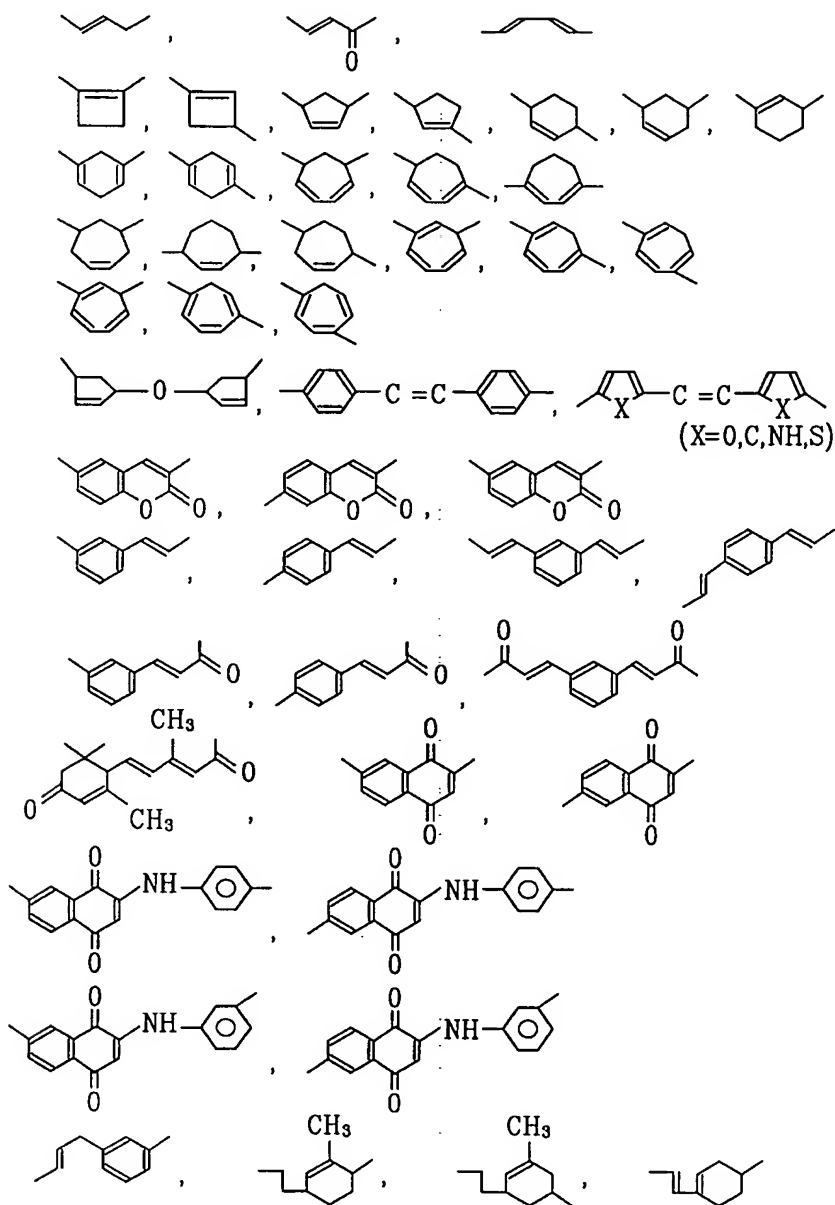
26. (Original) The method of claim 25, wherein the photo-alignment layer is formed of material having at least a photo-reactive ethenyl group at a polymer main chain, wherein the polymer is denoted by the following chemical formula 1:

{chemical formula 1}



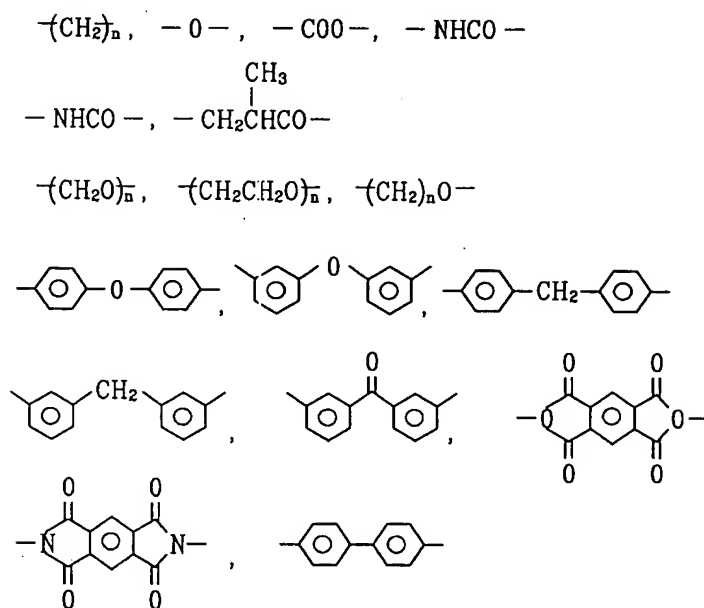
wherein subscripts a, b, and c denote a component ratio of respective monomers, wherein  $0 < a \leq 1$ ,  $0 \leq b < 1$ , and  $0 \leq c < 1$ , and wherein component A, a monomer including the photo-reactive

{Chemical Formula 2}



27. (Original) The method of claim 26, wherein components B and C are selected from groups shown in chemical formula 3, substituted-structure groups of chemical formula 3 with a halogen, cyano, nitro, amino group, other substituted-structure groups with carbonated groups of which carbon number n lies between 1 and 10 such as an alkyl, haloalkyl, and cyanoalkyl, and other carbonated groups of which carbon number lies between 3 and 8 such as an alkylaryl, haloaryl, haloalkyl aryl, nitroaryl, cyanoaryl;

{Chemical Formula 3}



28. (Original) The method of claim 25, further comprising:

forming a gate line and a crossing data line on the first substrate;

forming a thin film transistor at a crossing between the gate and data lines; and

forming a pixel electrode connected to the thin film transistor.

29. (Original) The method of claim 25, wherein the photo-alignment layer is formed by light-irradiation.

30. (Original) The method of claim 29, wherein the light-irradiation is irradiated at least once.

31. (Original) The method of claim 29, wherein a light used for light-irradiation is selected from a group consisting of unpolarized light, non-polarized light, linearly polarized light and partially polarized light.

32. (Original) The method of claim 25, wherein the rubbing alignment layer is selected from a group consisting of polyimide, polyamide, polyamic acid and SiO<sub>2</sub>.

Claims 33 and 34 (Canceled).